

(19)
(12)

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(43)

2003-0093519
2003 12 11

(21) 10-2002-0031098
(22) 2002 06 03

(71) 416

(72) 1167 523 1305

644 304

106 103

(74)

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(54)

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2 1 II-II' ,
3 2 ,
4 5 3 IV-IV' V-V' .

가 ,
가 가 가
(thin firm transistor array panel)
(disclination)
가 가 , ,
가 , , 가

가 , 가
가 가 가

1 2

1 II-II'

(110) 가

(121), (121) 가

(125) (121) 가

(110) (121) (123)

가 (131) (131) (133)

(190) (175) (133)

(190) (121)

(121, 125, 123) (131, 133)

(110) (SiN_x) (140) (121, 125, 123) (131, 133)

(125) (141, 142) n

(150) (150) n

(163, 165)

(163, 165) (140) (Mo) (Mo alloy) (Al)

(Al alloy) (121) (171), (171) (163)

(173), (171) 가

(179), (173) (123) (173)

(165) (133) (175)

(171, 173, 175, 179)

IZO 가 Al(Al)/Cr Al(A

I)/Mo(Mo)

(171, 177, 173, 175, 179) 가 (150) SiO:C

SiO:F (180) 가 (180) (19

0) (121) (171)

(180) (175) (179) (185, 189)

(140) (125) (182)

(803) (175) 5 (188)가 (125)

(179)가 (180)

(180) (185) (175)

(190) (112) (180) (52) (92)

(125) (179) (92) (182, 189)

(125, 179) (190) ITO(indium tin oxid

e) IZO(indium zinc oxide) (121) (191) 가 (190) (a1) (a2) (191)가 (121) (171) (121) (171) (pre-tilt angle) 가 (190) (191) 가 (190) 3 2 3 IV-IV' V-V' 4 5 (110) (123) (131) (190) (110) (121) (125) (131) (177) (190) (121) (121, 125, 123) (131) (SiN_x) (140) (121, 125, 123) (131) (152, 157) (152, 157) (140) (P) n p (ohmic contact layer) (163, 165, 167) (163, 165, 167) 1 가 (171), (171) (171) (173) 가 (179), (171, 179, 173) (123) (175) (131) (C) (173) (177) (131) (177) (171, 173, 175, 177, 179) (163, 165, 167) (152, 157) (171, 173, 175, 177, 179) (163) (171, 179, 173) (167) (177) (163) (15, 157) (C) (171, 173, 175, 177, 179) (163, 165, 167) (177) (167) (157) (152) (171, 179, 173), (165) (173) (175) (C) (163) (171, 173, 175, 177, 179) 가 (152) SiOC SiOF (180) (180) (175), (179) (177) (185, 189, 187) 가 (140) (125) (185) 가

.
(180)
) (175) (190) ITO IZO (185) (190)
(121) (171) (190)
(121) (171) (190) 가 (b2,
c2) (b1, c1) (121) (171) (a2, b2)
(190) 가 (121) (171)
(121) (171) (187)
(190) (177) (125) (179) (177)
(182, 189) (92) (97)가
(125, 179)

가

(57)

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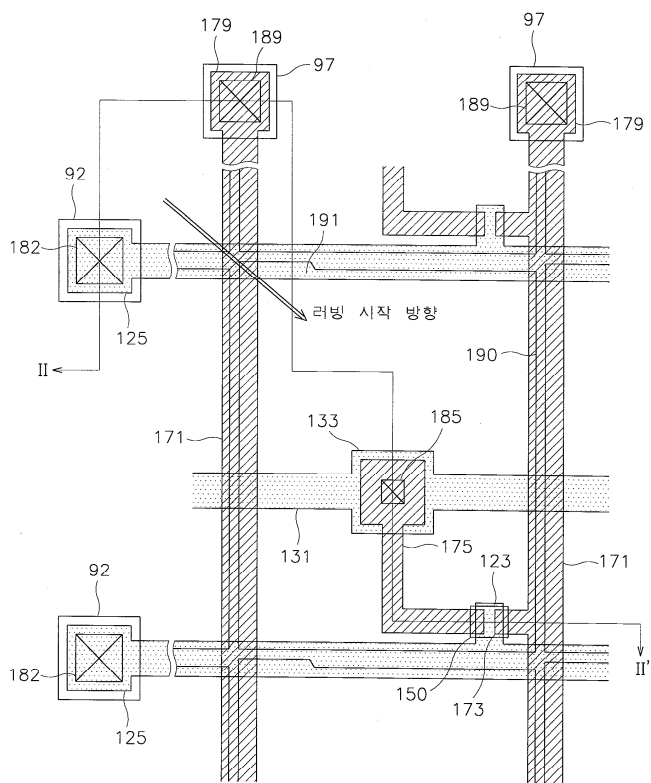
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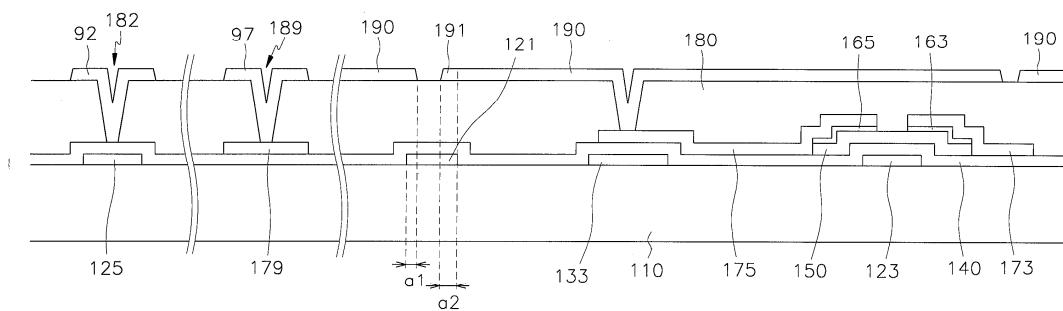
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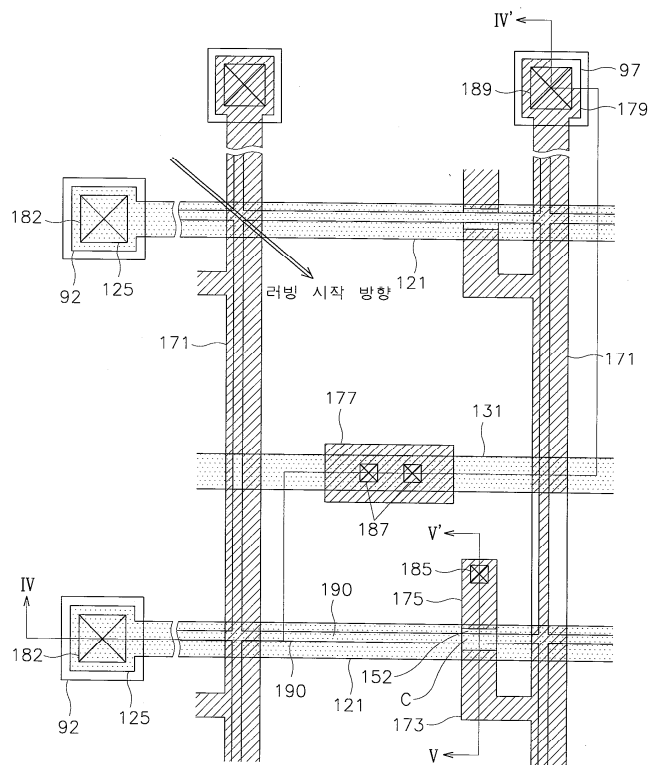
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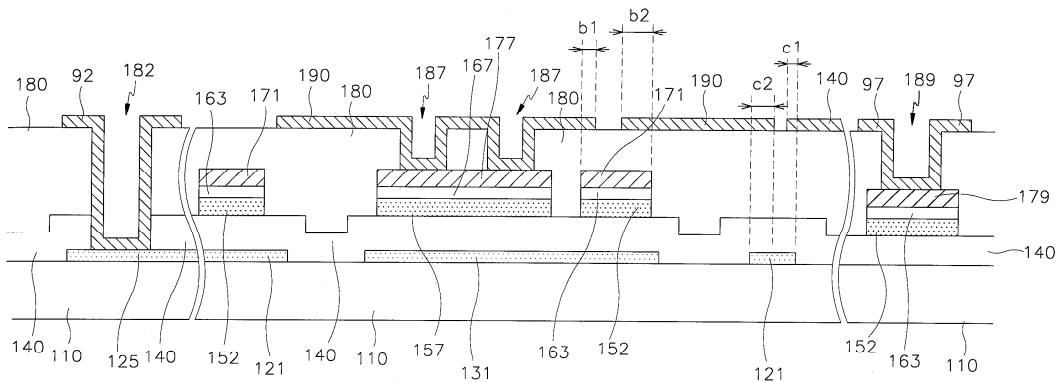
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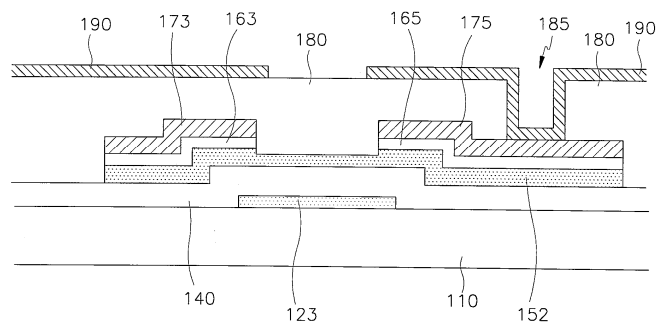
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专利名称(译)	一种用于液晶显示器的薄膜晶体管阵列基板		
公开(公告)号	KR1020030093519A	公开(公告)日	2003-12-11
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[标]申请(专利权)人(译)	三星电子株式会社		
申请(专利权)人(译)	三星电子有限公司		
当前申请(专利权)人(译)	三星电子有限公司		
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发明人	김동규 공향식 김장수		
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外部链接	Espacenet		

摘要(译)

用途：提供一种用于液晶显示装置的TFT阵列基板，使像素电极的边缘充分重叠，从而导致液晶分子与栅极线和数据线的排列破裂，从而阻止了光向栅极线和数据线的泄漏，从而防止了错位区域的产生。构成：一种用于液晶显示装置的TFT阵列基板，包括像素电极（190），所述像素电极（190）电连接至与栅极线（121）相交的数据线（171），以限定像素区域。像素电极在边缘部分与栅极线和数据线重叠。在每个单位像素区域的摩擦开始方向上，与栅极和数据线重叠的像素电极的边缘部分的宽度比与栅极和数据线重叠的边缘部分的任何其他宽度宽。

